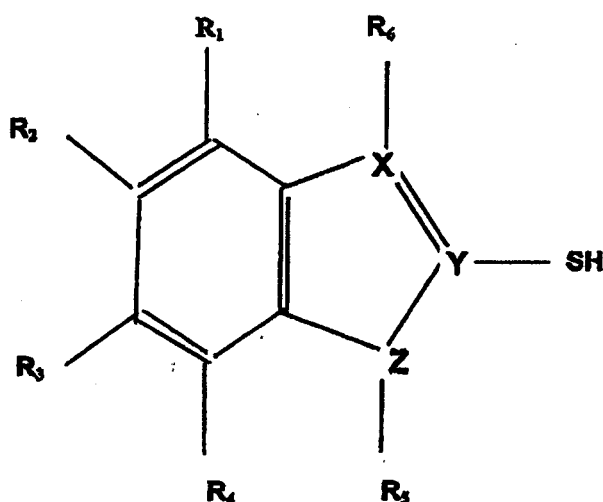


ABSTRACT OF THE DISCLOSURE

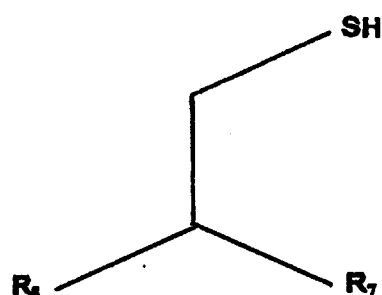
COMPOSITION AND METHOD COMPRISING SAME FOR REMOVING RESIDUE FROM A SUBSTRATE

A composition for removing residues and method using same are described herein. In one aspect, the composition comprises: an organic polar solvent; water; a quaternary ammonium compound; and a mercapto-containing corrosion inhibitor

5 selected from a compound having the following formulas (I), (II), 2-mercaptothiazoline, 3-mercaptopropyl-trimethoxysilane, and mixtures thereof:



(I)



(II)

wherein X, Y, and Z are each independently selected from C, N, O, S, and P; R_1 , R_2 , R_3 , R_4 , R_5 , and R_6 are each independently an alkyl group having a formula C_nH_{2n+1} ; R_7 is one selected from H, -OH, -COOH, and -NH₂; and R_8 is selected from an alkyl group having a formula C_nH_{2n+1} , or an alkanol group having a formula $C_nH_{2n}OH$; n ranges from 0 to 20; and the composition is substantially free of a water soluble amine. In another aspect, the composition comprises hydroxylamine wherein the mass ratio of hydroxylamine to quaternary ammonium compound is less than 3.